

Edge Isolation Tool (NT-2, BSET EQ)

- **Used for:**
 - Edge isolation of diffused Si wafers, dry texturing
- **Process Capabilities:**
 - Wafer loading capacity – Single wafer to stack of 150 wafers
 - Wafer Size – 125x125mm, 156x156mm, smaller wafers
 - Gases - SF₆, CF₄/O₂, N₂
 - RF Power Supply – 600W, 13.56 MHz
 - Rotating platform
- **Location:**
 - Second floor, NCPRE Fabrication Facility.
- **Contact:**

For any queries, please contact: sandeeps@ee.iitb.ac.in

